

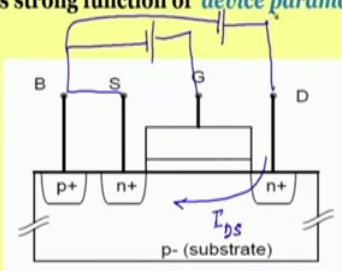
Analog Electronic Circuits
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Lecture – 11
Revisiting MOSFET (Contd.)


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Working Principle and Biasing of n-type MOSFET

- **V_{GS} and V_{DS} are applied :**
 - Current Flows through the V_{DS} :
 - I_{DS} is strong function of *device parameters*, W , L , V_{GS} and V_{DS}



p- (substrate)



So, welcome back here again the second part of today's module. What we are looking for it is the expression of the current as function of the W s and L s and V_{GS} and V_{DS} . And V_{GS} and V_{DS} of course, they are applied here. And also, just to get an idea that how this current is it depends on the device parameter.

So, in the next slide we will be seeing that how the current while the current it is flowing as I_{DS} how this I_{DS} current it depends on so these parameters.

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I-V Characteristic of n-type MOSFET

$V_{GS} > V_{th}$

$I_{DS} \propto \left(\frac{W}{L}\right)$

$\propto (V_{GS} - V_{th})$

$\propto V_{DS}$

$I_{DS} = K_n \left(\frac{W}{L}\right) (V_{GS} - V_{th}) V_{DS}$

$K_n = \mu_n \frac{E_{ox}}{t_{ox}}$

$V_{DS} \ll (V_{GS} - V_{th})$

$I_{DS} = ? \quad \frac{\mu_n E_{ox}}{t_{ox}} \cdot \frac{W}{L} \cdot (V_{GS} - V_{th}) \cdot V_{DS}$

So, what will be the expression of this I_{DS} ? So, we do have, so this is the big question. First of all let me quickly put the biases. For vertical field we do have V_{GS} here, so that creates vertical field. And let me assume that this V_{GS} it is higher than V_{th} . So, the first assumption is that this is higher than V_{th} ; that means, the channel is existing. And then we apply the other potential, so we do have the V_{DS} which is providing the lateral field.

Then, if you see here I think it is let me go with intuitive way that I_{DS} it is proportional to what? It is proportional to W . In fact, it will be proportional to W by L because if you see here this is the L and this is the orthogonal dimension it is the W . So, if you are having higher length for everything is remaining same it is expected that the resistance here it will increase. So, as a result the corresponding current it will decrease. So, on the other hand if the W is

increasing the corresponding resistance it will decrease. So, you may say directly that I_{DS} it is proportional to W by L or you can say that aspect ratio of the channel.

Now, how about the other parameters? So, this will be proportional to the conductivity in the channel regions which is controlled by this V_{GS} minus V_{th} which means that whatever the excess voltage you do have beyond the threshold voltage that is effectively contributing to the conductivity or it is helping to increase the conductivity in the channel. So, we can say V_{GS} is, V_{GS} minus V_{th} it is directly increasing this current. And also we do have the lateral field which is getting produced by V_{DS} , so we can also say that this is proportional to V_{DS} .

So, if I combine all of them, so what we can say here it is I_{DS} it is say proportionality constant say K W by L into V_{GS} minus V_{th} into V_{DS} , ok. And this K , this K it encapsulates whatever the device parameter is there in fact, this K if you see, if the mobility of the electrons are flowing in this way. So, if the mobility of the electron is higher of course, the current it will be better. So, mobility of the electrons is there. And also the dielectric constant of the oxide ϵ_{ox} divided by t_{ox} . So, intuitively you may say that this represents the capacitance of this structure which is per unit area of course.

So, for a given supply voltage here the amount of field it is getting created here it directly depends on this ϵ_{ox} divided by t_{ox} or I should say rather the amount of carrier it will be available it depends on this ratio. So, from that you can say that this K which is basically coming from the device parameter they can be directly written in this form. In addition to that of course, the device parameter is the V_{th} which is which of course, it depends on whatever the doping concentration is there in the substrate and so and so, but as the circuit designer you may assume that both K is constant V_{th} is also constant.

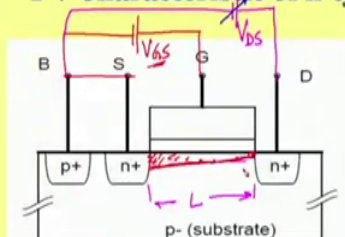
So, in summary what you can say that this expression of this I_{DS} it is $\mu \epsilon_{ox}$ divided by oxide thickness t_{ox} into W by L into V_{GS} minus V_{th} into V_{DS} . But one important thing we are missing here it is that, whenever we say that V_{GS} is higher than V_{th} and whatever the excess amount we have it is contributing for towards the conductivity of the channel, but this is valid probably in this portion. Then if I consider we are applying a voltage

V_{DS} which is say positive, that means, the voltage across this structure it is not same as the V_{GS} here. In fact, that supposed to be V_{GD} which is V_{GS} minus V_{DS} .

So, necessarily the conductivity of the channel towards this drain side and source side they are different. So, this equation it assumes that the V_{DS} is very small compared to V_{GS} minus V_{th} . And if the V_{DS} is going to be higher and higher or it is significant we need some correction in this equation. So, we are starting with this one with the assumption that V_{GS} is higher than V_{th} and also we assume that V_{DS} it is much smaller than V_{GS} minus V_{th} and then only this equation is valid. So, if we increase this V_{DS} let us see what is happening. So, let me go to the probably next slide.

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I-V Characteristic of n-type MOSFET (Contd...)



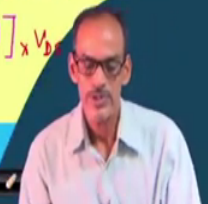
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$$I_{DS} = K \cdot \frac{W}{L} \cdot (V_{GS} - V_{th} - \frac{V_{DS}}{2}) V_{DS}$$

$$V_{GD} = V_{GS} - V_{DS} > V_{th}$$

$$V_{GD} = V_{th} \Rightarrow V_{DS} = V_{GS} - V_{th}$$

• For Significant V_{DS} , Conduction along "L" changes and hence.

$$I_{DS} = \left(\frac{\mu_n \epsilon_{ox}}{t_{ox}} \right) \cdot \frac{W}{L} \left[\frac{(V_{GS} - V_{th}) + (V_{GS} - V_{DS} - V_{th})}{2} \right] \times V_{DS}$$



So, what you are saying here it is the V_{DS} it is significant particularly compared to V_{GS} minus V_{th} . So, again let me put the quickly put the bias here V_{GS} and we do have the V_{DS} .

So, we do have whatever L and W s and all these things and as I said that if the length is, so it is sorry, the V_{DS} it is comparable with $V_{GS} - V_{th}$ then the conductivity along this length it is changing.

Hence, this I_{DS} its expression as I said need to be rectified or you need to be changed compared to whatever we have derived before. So, we are keeping the device parameter same as μ_n then ϵ_{oxide} t_{ox} and W by L those things it is remaining as is, but then the conductivity we need to change. So, let us see: what are the changes we need to make here.

Towards the source side we do have the $V_{GS} - V_{th}$. Whereas, on the on the other side on the other end namely towards the drain side we do have the V_{GD} which is $V_{GS} - V_{DS} - V_{th}$. So, we need to consider both this part as well as this part and on an average you may say that let me take average of it. So, we just simply add them divided by 2. So, what you are getting here it is we do have.

So, then I_{DS} let me write in this space is this part let me let you call this is K and then W by L , and then if you see here we do have two V_{GS} and then two V_{th} and divide by 2, but then V_{DS} is not there. So, we do have $V_{GS} - V_{th} - V_{DS}$. And, also along with that this is what it is contributing to the conductivity and then also we do have the V_{DS} appearing as it is providing the lateral field. So, we are applying V_{DS} also. So, we can multiply this by V_{DS} . So, you have V_{DS} by 2 here, this 2 it is coming there.

So, you may say that now the new equation it is like this and this is this is valid as long as $V_{GS} - V_{DS}$, it is which is actually V_{GD} it is higher than V_{th} . So, as long as this is getting satisfied then we can say that the expression of the current is like this. In other words, we can say that the channel is existing here as well as here, but of course, they do have a different strength. So, you may say that the strength of the channel is kind of tapered. So, here it is having strong conductivity, here it is weak.

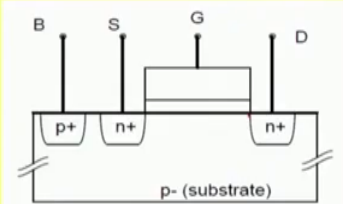
Now, what happens in a critical situation when we are just making this voltage higher and higher keeping this V_{GS} may be constant and such that the conductivity here it is approaching towards 0, which means that if it is V_{GD} it is exactly is equal to V_{th} then what

happens? In fact, till that point also this equation is valid. So, let me use this equation and let me let me put the condition that V_{GD} equals to V_{th} or you may say that V_{DS} . So, if I say this is equal, so we can say this is equal to V_{GS} minus V_{th} . So, then what happens?


So, this is what we will see in the next slide that if we are increasing this V_{DS} and if you are increasing such that this is just at the drain in the conductivity is approaching towards 0.

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I-V Characteristic of n-type MOSFET (Contd...)



• For $V_{GD} = V_{th} \Rightarrow V_{DS} = (V_{GS} - V_{th})$:

$$I_{DS} = K \cdot \frac{W}{L} (V_{GS} - V_{th} - \frac{V_{DS}}{2}) V_{DS} = K \frac{W}{L} (\frac{V_{GS} - V_{th}}{2})^2$$


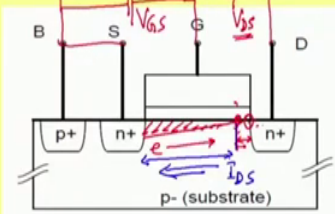
So, so that is what we are saying here that what happens if the V_{GD} equals to V_{th} sorry this comma should not be there. So, V_{GD} if it is equal to V_{th} which implies, that V_{DS} is equal to V_{GS} minus V_{th} and then what we have the current expression is K into W by L and then V_{GS} minus V_{th} minus V_{DS} by 2 multiplied by V_{DS} . Now, this V_{DS} we can replace by V_{GS} minus V_{th} , so that gives us the expression here it is K W by L into; so, this portion it is V

$V_{GS} - V_{th}$ here also we do have $V_{GS} - V_{th}$ here we do have divided by 2. So, this portion it becomes $V_{GS} - V_{th}$ by 2.

And we do have V_{DS} which is also $V_{GS} - V_{th}$. So, directly you can say this is square. And this is this is what it is happening when at this point the channel is about to disappear. This is referred as something called pinch off will not be going in detail of that, but till this point you may say that this equation of this current is valid. If I take this V_{DS} beyond this point then what happens? So, again let me let you consider this equation in the next slide and then we will see what other things are happening there.

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I-V Characteristic of n-type MOSFET (Contd...)




$$\frac{1}{(L - \Delta L)} = \frac{1}{L \left(1 - \left(\frac{\Delta L}{L}\right)\right)}$$

$$= \left(1 + \frac{\Delta L}{L}\right) \leftarrow f V_{DS}$$

$$\left\{ V_{DS} - (V_{GS} - V_{th}) \right\} = \frac{L}{(1 + \lambda V_{DS})}$$

• For $V_{DS} > (V_{GS} - V_{th})$:

$$I_{DS} = \frac{K W}{2 L} (V_{GS} - V_{th})^2 = \frac{K W}{2 (L - \Delta L) L} (V_{GS} - V_{th})^2 (1 + \lambda V_{DS})$$


So, if the in this condition if I take the V_{DS} higher than $V_{GS} - V_{th}$; so, if I consider equal then whatever the equation we do have K into W by L $V_{GS} - V_{th}$ square divided by 2. Now, if we exceed this one what is happening is of course, in this portion the channel is

disappearing, so obviously, thinks it will be the obvious conclusion or maybe will be having the tendency that we may say that the current is not flowing, right and however, we do have the lateral field V_{DS} .

So, if the current is not flowing then of course, from here to here there is no potential drop. So, then what happens? They will the channel will completely break or what will happen? Practically, what happens is that the channel is here it may be going till some point which may not be really going to the drain end. So, you may say that the point where the channel it is satisfying a condition that the voltage across this structure it is exactly equal to V_{th} . You may say that till this point or till the left side of this point the channel is existing and beyond this one the channel is not existing.

The natural question is that then how the current is flowing. Of course, there will be a current flow because this voltage major part of the voltage it will appear across a small length or I should say small region of this length and as a result there will be a very strong field. So, you may say that this portion of the device it is working as same as whatever the device we have discussed here where at this age the conductivity is approaching to 0 and whatever the current is flowing here whatever the injection of the carriers are happening that carriers are basically jumping across this junction from the pinch of point till the age of the drain. As a result you may say that the total current while the electrons are moving in this direction the total current is essentially defined by, so this I_{DS} it will be defined by whatever the current is flowing say through this device and now the device it is getting modified namely its length is getting shortened.

So, you may say that this equation it is again valid even in this condition only thing is that instead of L I will be having shorter length. So, let me write that we do have $K W$ and also 2 here and then L minus shrinkage of the length say ΔL , rest of the things it is remaining same. So, $V_{GS} - V_{th}^2$; so, then you may say that I do have ΔL and how do I express from outside. Of course, this ΔL it is getting created by this V_{DS} . So, naturally this ΔL it is a function of V_{DS} .

So, we may write this L minus ΔL as like this, you can take you can take the L outside, you can make it 1 minus ΔL divided by L in the denominator and then if you take, so that is the denominator part and then if you take in the numerator what you can say it is 1 by L is remaining there if I assume that this part it is very small compared to 1 , so by Taylor series expansion you may take it only one part of it. Let me say that 1 plus ΔL divided by L . And this ΔL part it is a strong function of V_{DS} . Since this portion is very small again it is normal it is considered as 1 plus λ into V_{DS} divided by L .

So, you may say that this part this part it is getting replaced by this. In other words we may say that instead of this one let me directly write L here and let me put this factor 1 plus λ into V_{DS} . In fact, this is what the equation normally we frequently use and the condition here is of course, the device it is in this region referred as saturation region will be discussing that pretty shown. But please make a note that going from this point to this point it is having some discontinuity if you carefully look into the equation instead of writing this V_{DS} I should have written this is V_{DS} minus whatever the limiting value and then only there will be continuity of then only we will be having continuity of the equation from the previous region to this region.

However, most of the time we considered that this part it is may be small compared to V_{DS} , so we do approximate this whole thing by λ into V_{DS} . And, if you see that this is the limiting value of the V_{DS} up to which it was having different kind of behavior and if you go beyond this one, the characteristic it is all of a sudden it is having a change. So, we will see that these two regions are having distinct behavior. So, we will be looking into that in detail while will be comparing this characteristic in the across the two regions of operation in the subsequent slides.

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Summarization of I-V Characteristic of n-type MOSFET

- For $V_{GS} < V_{th}$:
 $I_{DS} \approx 0$
- For $V_{GS} > V_{th}$ and $V_{DS} < (V_{GS} - V_{th})$:
 $I_{DS} = \mu_n \frac{C_{ox}}{L} \frac{W}{2} (V_{GS} - V_{th}) V_{DS}$
- For $V_{GS} > V_{th}$ and $V_{DS} > (V_{GS} - V_{th})$: $V_{D(sat)}$
 $I_{DS} = \frac{\mu_n C_{ox}}{2} \frac{W}{L} (V_{GS} - V_{th})^2 (1 + \lambda V_{DS})$

So, if we summarize what we said is that the device characteristic it is, it can be said it is having different regions of operation. Again quickly we do have the V_{GS} here and we do have the V_{DS} here. So, that is producing rather that is V_{GS} is generating the channels, the electrons are moving in these directions and the consequence is that the current is flowing in this direction.

Note that the channel is basically getting created by the electron layers and of course, along with the electron layers we do have the static ions. Those static ions are working as depletion region beyond the channel region, but they do not participate for the current flow, so current is basically carried by the electrons.

Anyway, so the I_{DS} while this I_{DS} is flowing here from terminal side we will see this is the I_{DS} . So, as circuit designer we may not be knowing what other things are happening

internally, but from the terminal what we can say that some current is flowing and that current is coming back here, and this current is getting produced by the combination of V_{DS} and V_{GS} . So, let us see for this I-V characteristic for different conditions of these voltages and let me summarize that.

First of all if the V_{GS} is less than V_{th} , so we assume that this channel it is almost very weak and you may say that instead of saying equal we may say approximately equal to 0. On the other hand, when the V_{GS} is higher than V_{th} and then we are applying V_{DS} is positive, but it is less than this critical voltage, we may say that it is less than the V_{GS} minus V_{th} which means that even at the drain side we do have the channel may be the channel is stronger here may be here it is weaker.

But finally, finally, we do have the channel is spreading across the length and with that condition we may say that the current here it is $K \cdot W$ by $L \cdot (V_{GS} - V_{th} - V_{DS})^2$ multiplied by V_{DS} . And of course, this K it is having its own internal device parameter, namely mobility then dielectric constant of the oxide, thickness of the oxide. On the other hand, if the V_{GS} is say higher than V_{th} however, V_{DS} is higher than $V_{GS} - V_{th}$ in fact; this is referred as $V_{D sat}$.

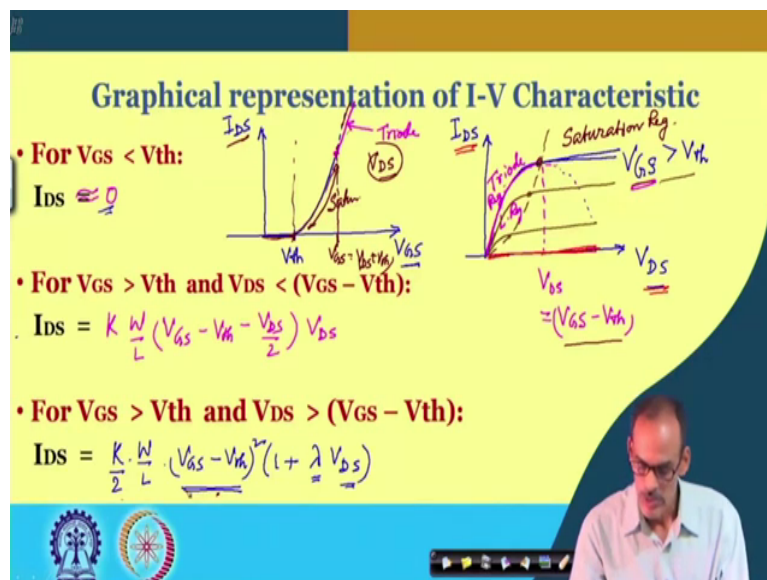
Of course, this is this is not constant it depends on the V_{GS} sometimes it is referred as $V_{D sat}$ we will see that why it is called $V_{D sat}$, but whatever it is if the V_{DS} is beyond this one indicating that pinch off already happened towards the near the drain end and the current it is it hardly depends on V_{DS} and the corresponding expression of the current it is K into W by L into $(V_{GS} - V_{th})^2$ by 2 and in addition to that we do have $1 + \lambda \cdot V_{DS}$, ok.

So, ideally as I say that I should have written $V_{DS} - V_{D sat}$, but all practical purposes most of the time we write V_{DS} . So, this is what the overall I-V characteristic equation of the transistor and if you see here what are the parameters we do have a device parameter, of course, this is one device parameter and then we can say this is also device parameter and also

we do have device parameter here. So, these are basically device parameters. The rest of the things are the voltages and the device dimensions.

And as I said that for board level design if the device it is already implemented which means that W and L of the device it is already implemented, then as a circuit designer will be having flexibility to change this V_{GS} and V_{DS} to get a meaningful current flow. So, that is the I-V characteristic. Now, let us look into if I combine all these equations if we consider the graphical interpretation of the this I-V characteristic and the next slide, so let us see the graphical interpretation of that.

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First of all under this condition as I said this current is approximately 0, this is K into W by L quickly, K into W by L V_{GS} minus V_{th} minus V_{DS} by 2 into V_{DS} and then here we do have K into W by L divided by 2 V_{GS} minus V_{th} squared into 1 plus lambda into V_{DS}. So,

if you plot this current I_{DS} as function of V_{GS} and V_{DS} what you can see here, this is of course, it is 0. So, now if we consider this region so probably you can consider two cases. So, let me keep the V_{GS} constant and then let you observe I_{DS} as function of V_{DS} and assuming this V_{GS} is constant, but higher than V_{th} .

So, this equation indicates that V_{DS} is appearing here in square form and in fact, it is parabolic relationship. So, if the V_{DS} it is small and if it is smaller than V_{GS} minus V_{th} then you may say that it is going like a parabolic way. So, this is the equation, I should use the other color to represent this characteristic curve. So, this equation it is getting reflected here. But then this equation is valid till this point where V_{DS} equals to V_{GS} minus V_{th} and if you go beyond this point the current it hardly depends on V_{DS} in fact.

Typically, this λ is very small, so you may say that if I ignore this part the current supposed to be remaining constant. And, if I consider some small that the actual value of the λ it may be having slight slopey kind of things which means that this change is representing the effect of this λ which is referred as channel length modulation affect. The channel length is getting modulated by V_{DS} ; in fact, this is similar to base width modulation of the BJT we have considered.

So, if you see here the different regions of operation from this point beyond the current is getting saturated. So, here we may say that this is saturation region. So, saturation region of operation and before that it is referred as triode region, triode region. Because the current depends on both V_{GS} and V_{DS} sometimes it is also referred as linear, particularly if you see this portion the device behaves like a linear, so either we may say it is triode region or linear region.

Now, this is for a given value of the V_{GS} . Now, if I change this V_{GS} to some other value of course, this point it will be changing. So, if I decrease this V_{GS} , but still maintaining this is higher than V_{th} we may get lower current and the corresponding current profile it will be like this and so and so. So, the boundary between saturation and triode region; however, for smaller value of this V_{GS} it will come down like this.

So, you may say that the boundary between this linear and saturation region it is having like this equation. In fact, this is a quadratic equation. We will see that what is why it is really a quadratic equation. If you make this V_{GS} smaller and smaller in fact if we take it further down. So, what it will happen is that current it will be almost getting 0; that means, the corresponding characteristic it will be coinciding with V_{DS} line. So, this characteristic it is referred as I_{DS} versus V_{DS} characteristic.

Now, if you see say this equation, in fact, you can try to plot the I_{DS} versus V_{GS} also for a given value of V_{DS} . To start with let me consider the device it is in for a given value of V_{DS} . So, if I increase the V_{GS} beyond V_{th} then only the current it will flow, but before that the current is approximately 0. And if you if you are increasing this current sorry, if you are increasing this V_{GS} keeping the V_{DS} constant and then you may say that the device starts from this region or saturation region and hence the dependency it is like a quadratic.

And, if you go beyond some point where probably we are satisfying rather this condition instead of this one and the device instead of really going like this it will bifurcate from that and it may continue to be like a linear one. So, from this point onwards the device enters into triode region or linear region. And before this point the device it was in saturation region. So, here the device it is in saturation region.

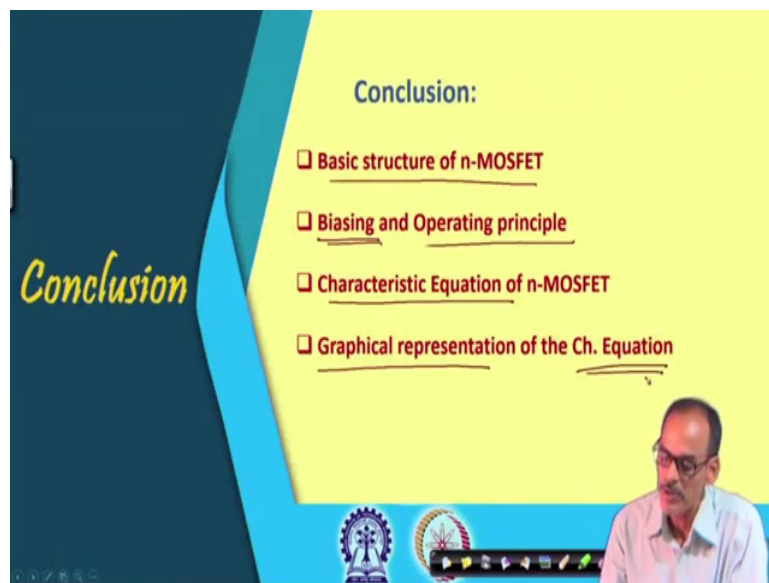
So, this is happening for a given value of V_{DS} . So, which means that this point it is at this point the V_{DS} equal to V_{GS} minus V_{th} or rather you may say that V_{GS} equals to V_{DS} plus V_{th} , right. So, naturally if I increase this V_{DS} , I will be getting another characteristic curve where this bifurcation it will be probably starting beyond this point and so and so. So, normally these changes we can hardly see. So, in most of the textbook it says that, this is quadratic equation.

Note that this till this point the current is 0, only the current is flowing beyond this one and the boundary of between this triode and saturation region it is nothing, but this portion because this character the boundary point it is nothing, but the V_{GS} minus V_{th} curve. So, you may say that triode and saturation boundary is nothing, but this profile and this profile it

is obtained from this equation where I_{DS} is basically proportional to $V_{GS} - V_{th}$ square. So, that is about the graphical representation.

So, let us see: what are the things we have covered today or rather so far we have discussed in this topic.

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We have discussed the basic structure of the n-MOSFET, and then we also have discussed about the operating principle of the circuit for different biasing situation. And, then we have discussed about the I I - V characteristic of the MOSFET, and then we have discussed about the graphical representation of the I - V characteristic equation.

Note that, whatever the equation we have obtained here it is not having really a diode kind of equation, but we will be having a tendency to utilize those characteristic equation to represent

in the form of you know equivalent circuit. So, later we will see that how those equation can be used to represent the device by means of electrical circuit modules. So, that will be discussed in detail whenever will be going to actual circuit containing MOSFET.

So, in the next module, similar discussion it will be there as we have discussed today, but then for PMOS transistor. I think that is all today.

Thank you for listening.